Study on He processing and HPR for recovery from field emission

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TTC topical meeting on SRF cryomodule clean room assembly

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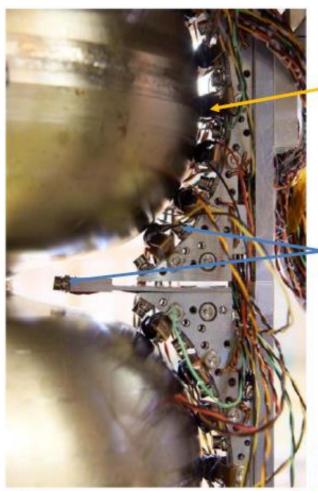
Motivation of study

- For recovering from bad performance of cavities, there are several ways;
 - in situ: He processing, RF processing
 - not in situ: HPR, EP, CP
- It is reported that He processing is effective. But it also could be risky. We want to know
 - what is happening during He processing?
 - how is it effective or risky?
 - what is safe/stable procedure of He processing?
- HPR is also effective to recover from field emission.
 - How is HPR effective?
 - Don't we need EP or CP to perfectly remove F.E. source?

History of KEK-ERL #2 cavity

VT	date	Surface treatment etc.	Aim of VT
1st VT	2010/Sep	EP(100um), Annealing,EP2(20um), HPR, Baking	Performance check
2nd VT	2010/Dec	EP(20um), HPR, Baking	Performance check
3rd VT	2011/Jan	Warm-up	Check Q-value after warm-up
4th VT	2012/Jul	HPR (assembly input and bottom flanges)	HPR study
5th VT	2013/Jul	Keep with vacuum condition	Check reproducibility
6th VT	2014/Aug	Ar purge (No flange assembly)	Check Ar purge procedure
7th VT	2014/May	(Warm-up)	System check of He processing (0)
8th VT	2014/Jun	(Warm-up)	Study on He processing (1)
9th VT	2014/Sep	Flange disassembly/assembly	Check flange disassembly/assembly procedure
10th VT	2014/Oct	(Warm-up)	Study on He processing (2)
11th VT	2014/Nov	HPR (assembly all flanges)	HPR study

X-ray mapping system



82 PIN diodes and 93 Carbon resistors are mounted on the mapping system along a meridian to detect 9cell radiation and temperature mapping precisely

Details of mapping PIN (iris) PIN(up1) Resister (0 degree up1) PIN(up2) Resister (0 degree up2) Carbon PIN(up3) resister Resister (0 degree up3) PIN(up4) Resister (0, 90, 180, 270 degrees) cell PIN(down1) Resister (0 degree down1) PIN(down2) Resister (0 degree down2) PIN(down3) Resister (0 degree down3) PIN(down4)

PIN diode

PIN diodes (HAMAMATSU S1231) for X-ray mapping with current Amplifier



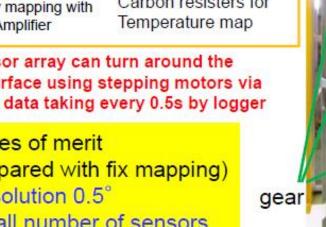
PIN (iris)

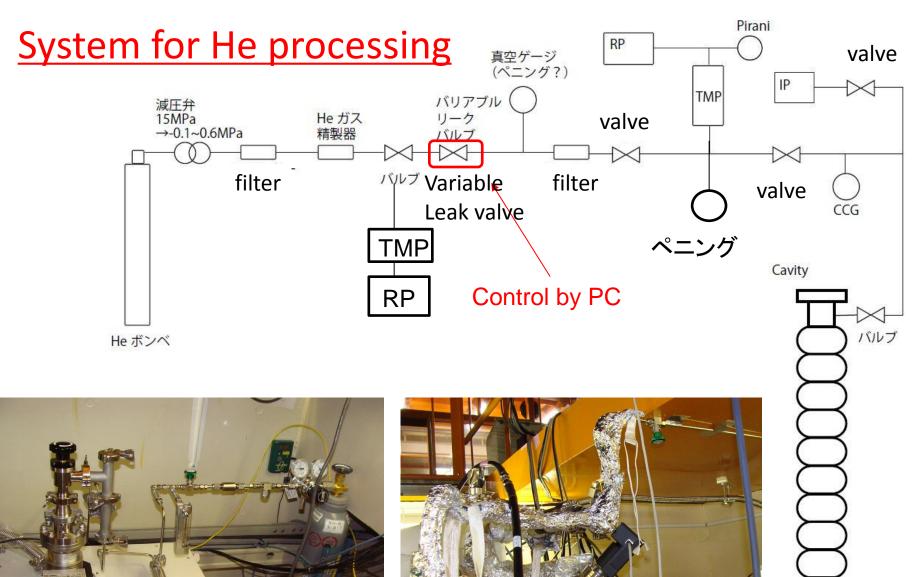
Carbon resisters for

The sensor array can turn around the cavity surface using stepping motors via gear and data taking every 0.5s by logger

Figures of merit (compared with fix mapping)

- Resolution 0.5°
- Small number of sensors





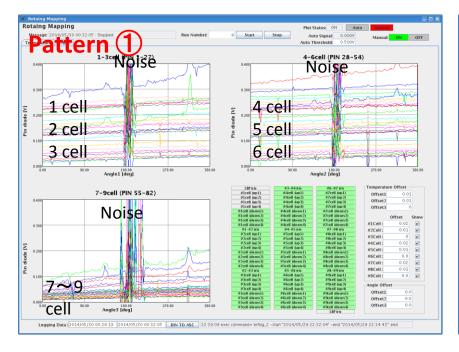


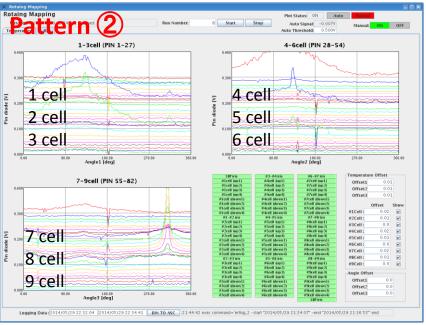


Two status during He processing

Two status appear during He processing

- 1 Radiation all over cavities. ~All surface mode~
 - Like discharge? Plasma?
 - It occurs at vacuum level around 10^-2 Pa.
- Radiation are strongly activated. ~Enhanced mode~
 - Some emitters can be activated. But some can not.
 - It occurs at vacuum level of $10^{-3} \sim 10^{-4}$ Pa.

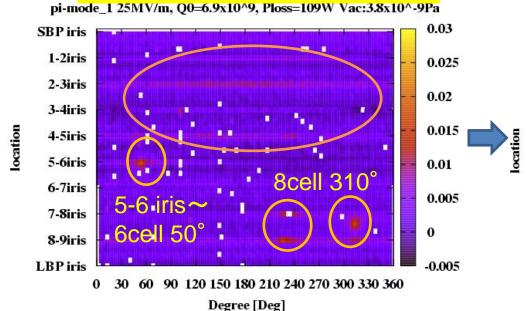




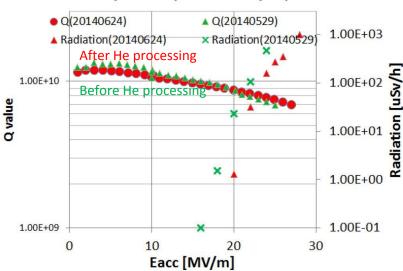
He processing trial (0&1)

- 3 emitters could be observed before He processing.
- 2 emitters remained and 1 emitter disappeared after He processing.
- •emitter seems to disappear after several ten minutes of "enhanced mode"
- Q-value recover little bit and radiation on-set increased.

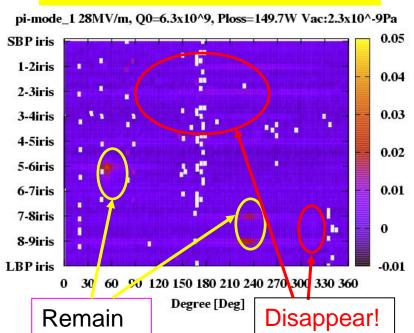
Before He processing :10^-8Pa

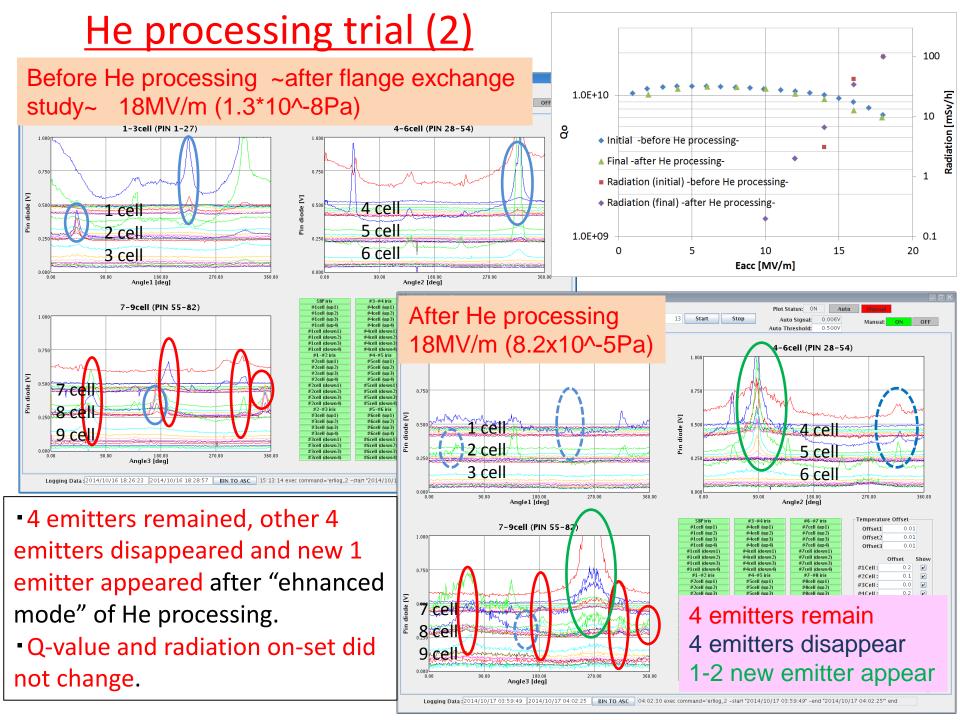


pi-mode (June 24 -May 29)



After He processing: 10^-8Pa

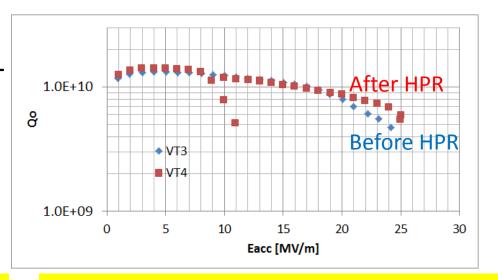




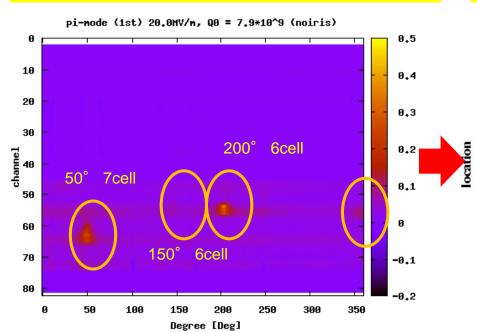
Study on HPR (1)

Comparison between 3rd & 4th VT

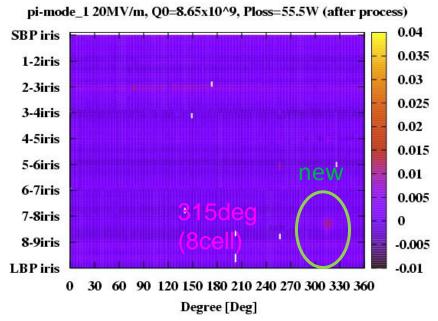
- HPR was applied.
- Emitter observed at 3rd VT were disappeared.
- Q-vaule, Eacc > 20MV/m, recovered



3rd Vertical test pi-mode (20MV/m)



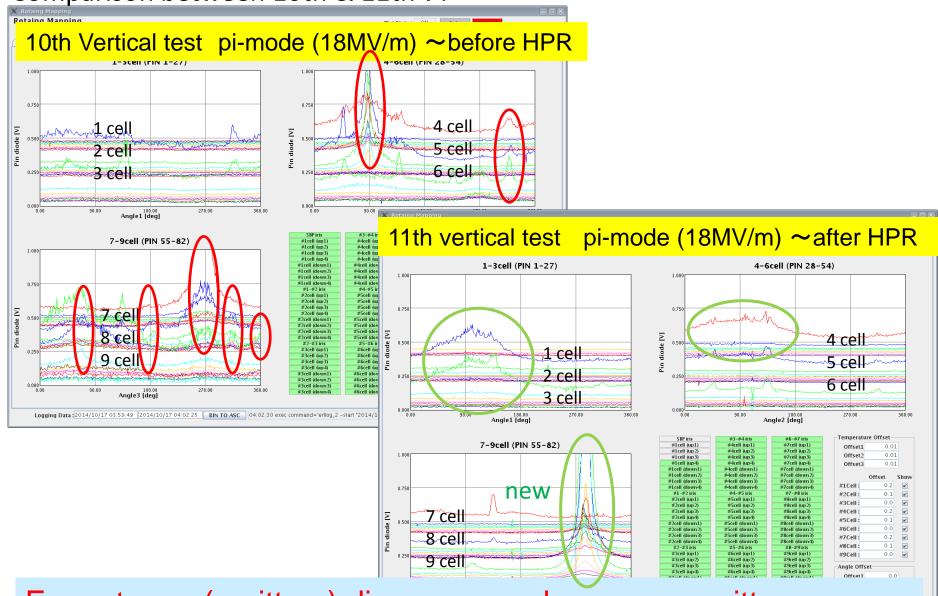
4th vertical test (this) pi-mode (20MV/m)



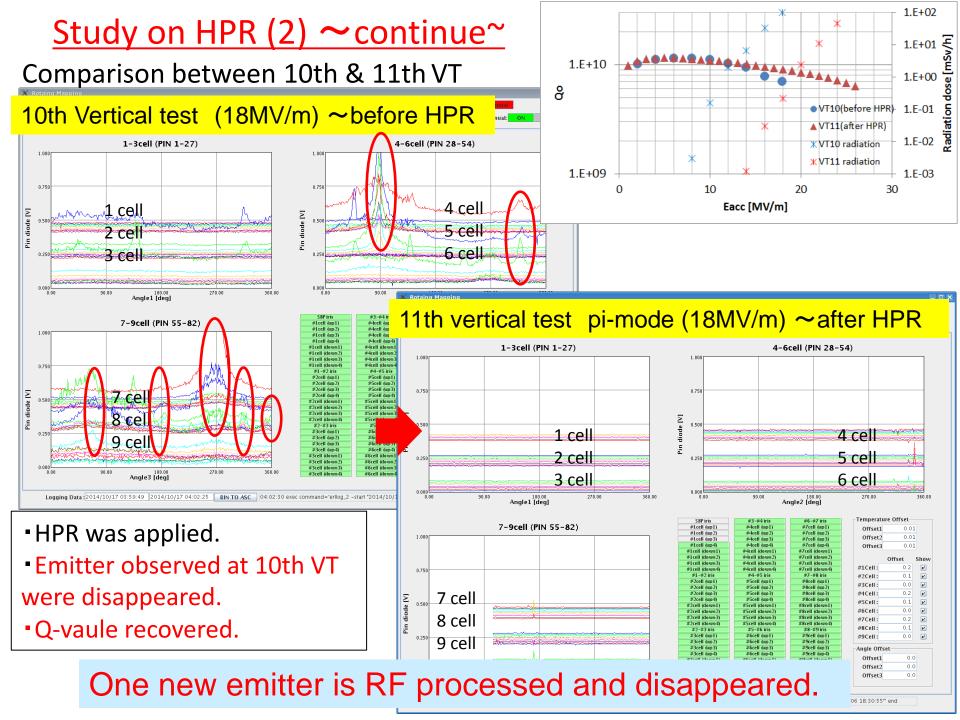
Every traces(emitters) disappear and one new emitter appears

Study on HPR (2)

Comparison between 10th & 11th VT



Every traces(emitters) disappear and one new emitter appears



<u>Summary</u>

[He processing]

- We tried He processing at vertical test.
 - Conditioning time is limited by radiation safety and He consumption.
- Two states of enhanced radiation status were observed. →
 Which is "so called" He processing at other labs?
- At moment, our statistics are too small to make conclusion.
 However, it indicates;
 - "enhanced mode" seems to be effective,
 - about half of emitter could be processed,
 - sometimes new emitter appear.
- Anyway we will collect more data.

[HPR]

- Tried twice. Both cases, observed emitters were removed after HPR.
- It indicates HPR is effective to remove field emission sources. → But also need more statistics.